

Amendments to the Specification:

Please replace the paragraph beginning on page 14, line 1 with the following rewritten paragraph:

--Very fine particles obtained in accordance with the invention may further be printed, coated, or otherwise deposited on a substrate upon expansion of the supercritical fluid mixture in processes similarly as described in concurrently filed, copending, commonly assigned USSNs 10/815,026

~~_____ (Kodak Docket No. 87485) and 10/815,010 _____~~

~~(Kodak Docket No. 87486)~~, the disclosures of which are incorporated by reference herein. Since the process of the present invention produces fine powder that is comparable to those produced by RESS techniques, RESS –based thin film deposition techniques (including method and apparatus, with minor changes to account for low level of organic solvent present in the supercritical mixture) may also be employed for the particles produced by the present invention. For example, after formation of particles in a particle formation vessel by SAS type process in accordance with the invention, the resulting mixture of very fine (less than 100 nanometers, preferably less than 50 nanometers, most preferably less than 10 nanometers) precipitated particles and compressed supercritical fluid may be expanded under controlled conditions and thin films of the particles may be coated on a substrate, similarly as in the RESS (and other similar) type coating processes described in U.S. Patent Nos. 4,582,731, 4,734,227, 4,734,451, 4,970,093, 4,737,384, 5,106,650, and Fulton et al., Polymer, Vol. 44, 3627-3632 (2003), the disclosures of which are incorporated by reference herein.

Condensation of solvent from the supercritical fluid, solvent, and precipitated solute mixture upon expansion of the mixture may be avoided or minimized, if desired, by selection of a solvent with sufficiently high vapor pressure, and/or control of the temperature and pressure of the expansion chamber.--